

INFORMATION DISCLOSURE CITATION

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Applicant	Ogasawara et al.		
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U.S. PATENT DOCUMENTS							
Examiner Initial*	Document Number	Issue Date	Name	Class	Sub Class	Filing Date If Appropriate	
HP	5,315,123	5/1994	Itoh et al.				
HP	5,285,075	2/1994	Minamide et al.				
HP	5,136,169	8/4/92	Smith et al.				
HP	4,808,829	2/1989	Okumura et al.				
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HP	4,376,249	3/1983	Pfeiffer et al.				
HP	4,199,688	4/1980	Ozasa				

FOREIGN PATENT DOCUMENTS							
	Document Number	Publication Date	Country	Class	Sub Class	Translation Yes or No	
			None				

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)	
HP	Goodberlet et al., "Spatial-Phase-Locked Electron-Beam Lithography with a Delay-Locked Loop," J. Vac. Sci. Technol. (1997), B15(6): 2293-97
HP	Smith et al., "A New Approach to High Fidelity E-Beam and Ion-Beam Lithography Based on an <i>in situ</i> Global-Fiducial Grid," J. Vac. Sci. Technol. (1991), B9(6):2992-95
HP	Smith et al., "Application of Moiré Techniques in Scanning-Electron-Beam Lithography and Microscopy," J. Vac. Sci. Technol. (1975), 12: 1262-65

Examiner	<i>HP han</i>	Date Considered	<i>11/04</i>
*Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.			
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